

1/5

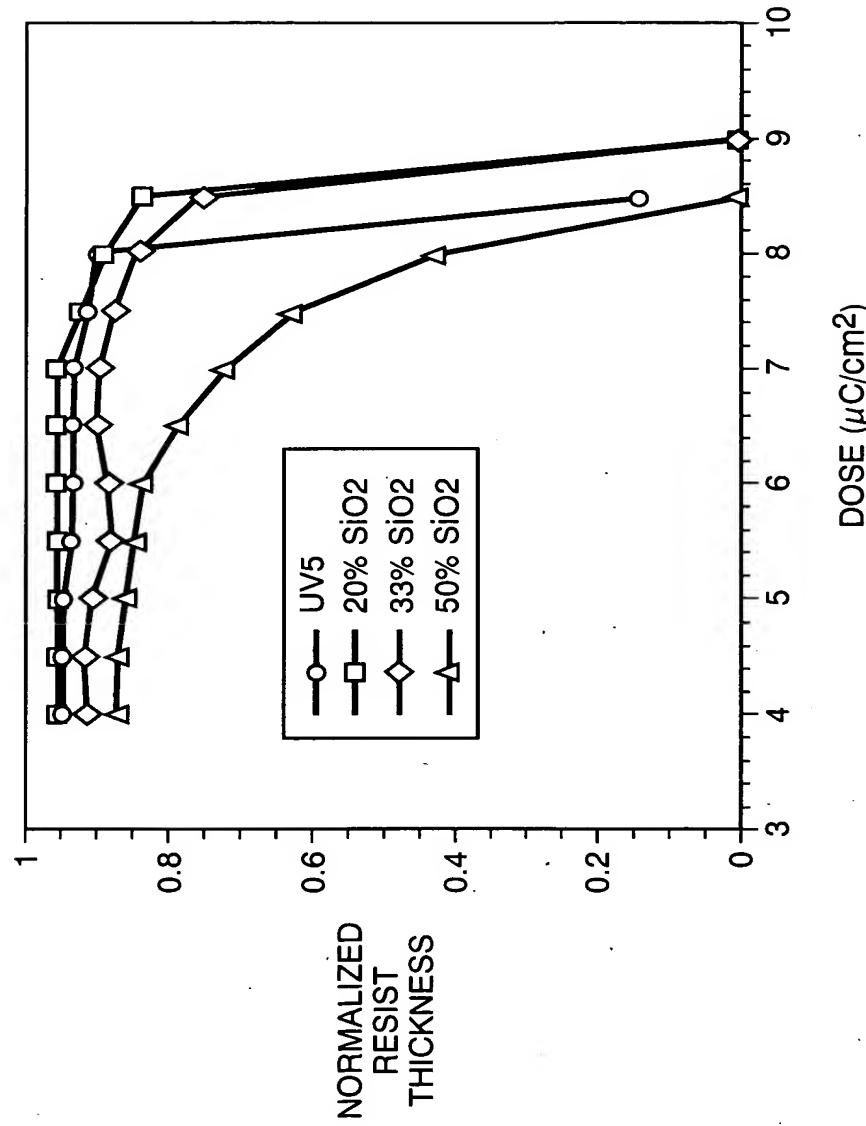
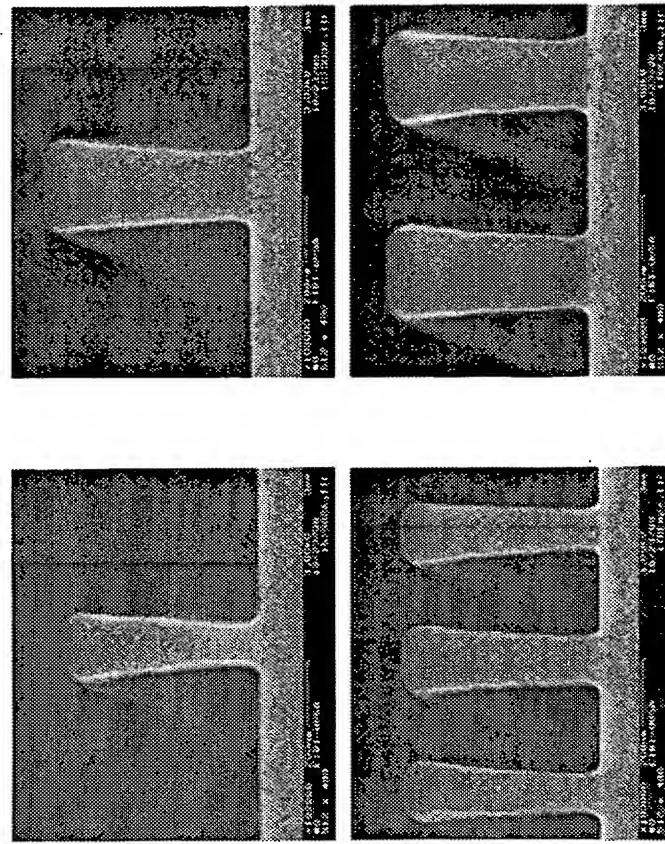


FIG. 1



Best Available Copy

UV5 RESIST COMMERCIAL ORGANIC RESIST

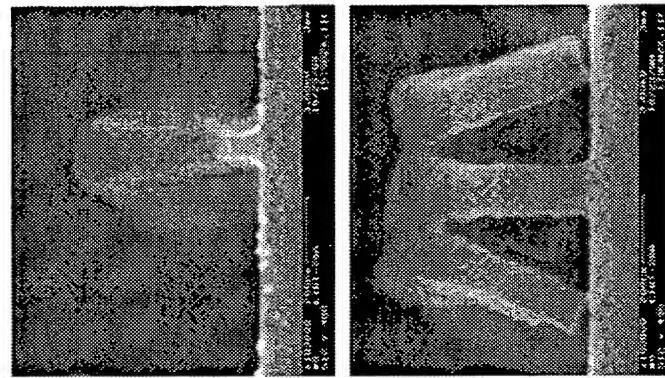


300 nm

200 nm

FIG. 2

EXPERIMENTAL 20% SiO₂ EIRT RESIST



200 nm

300 nm

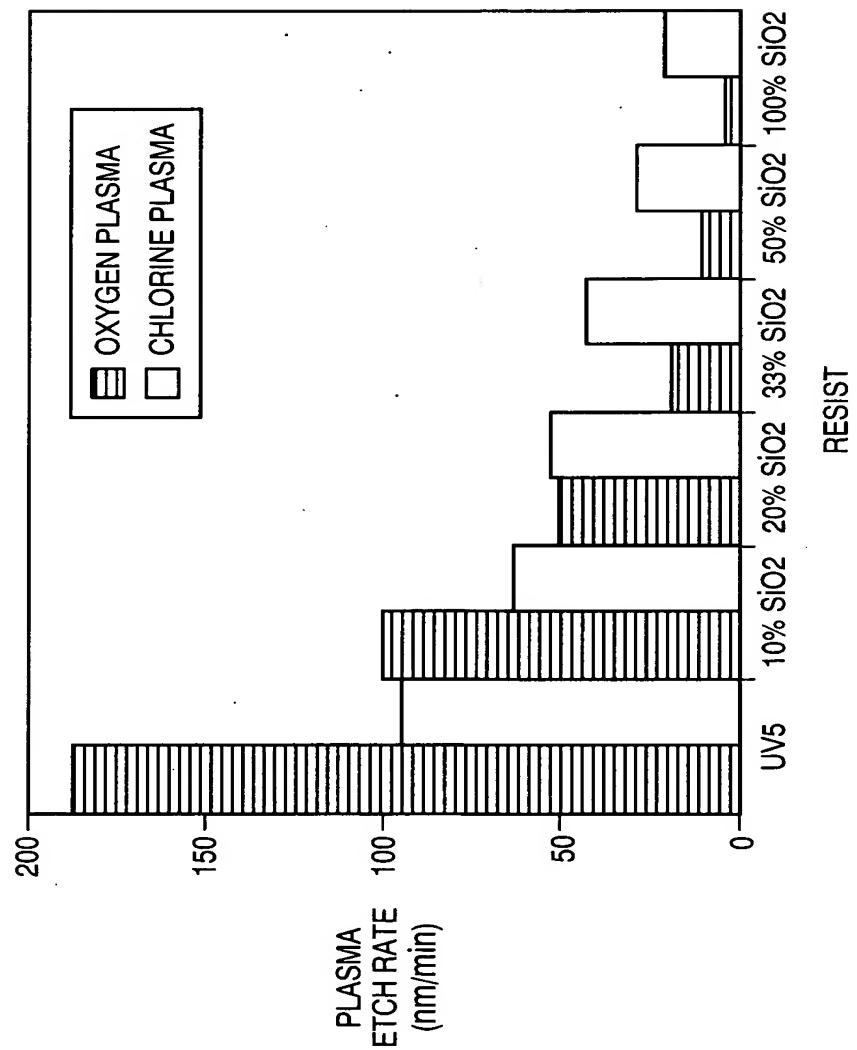


FIG. 3



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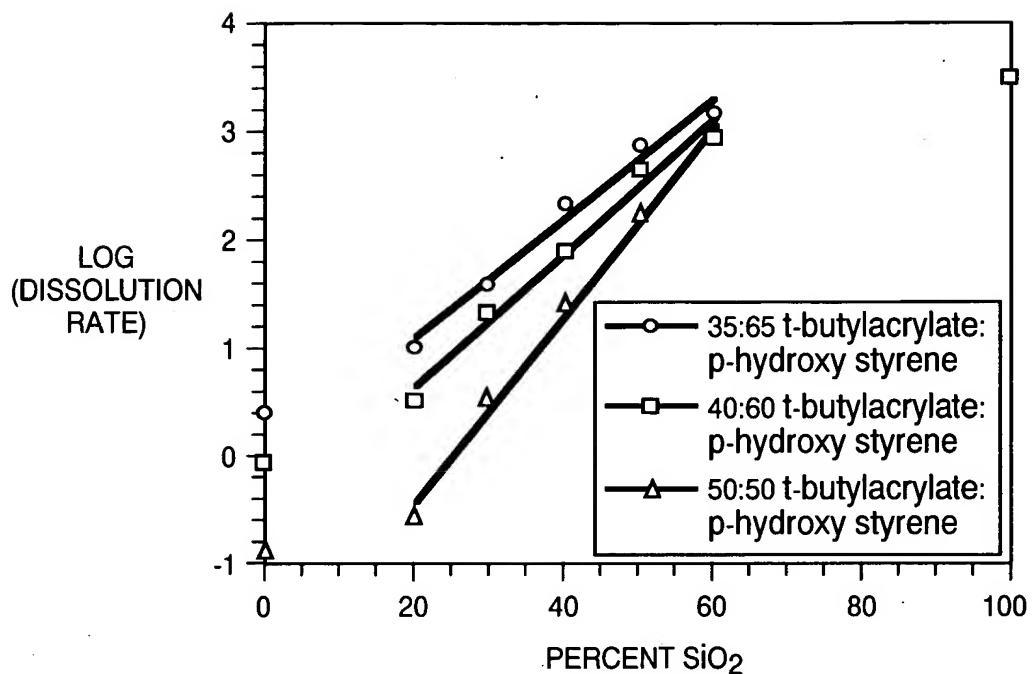


FIG. 4

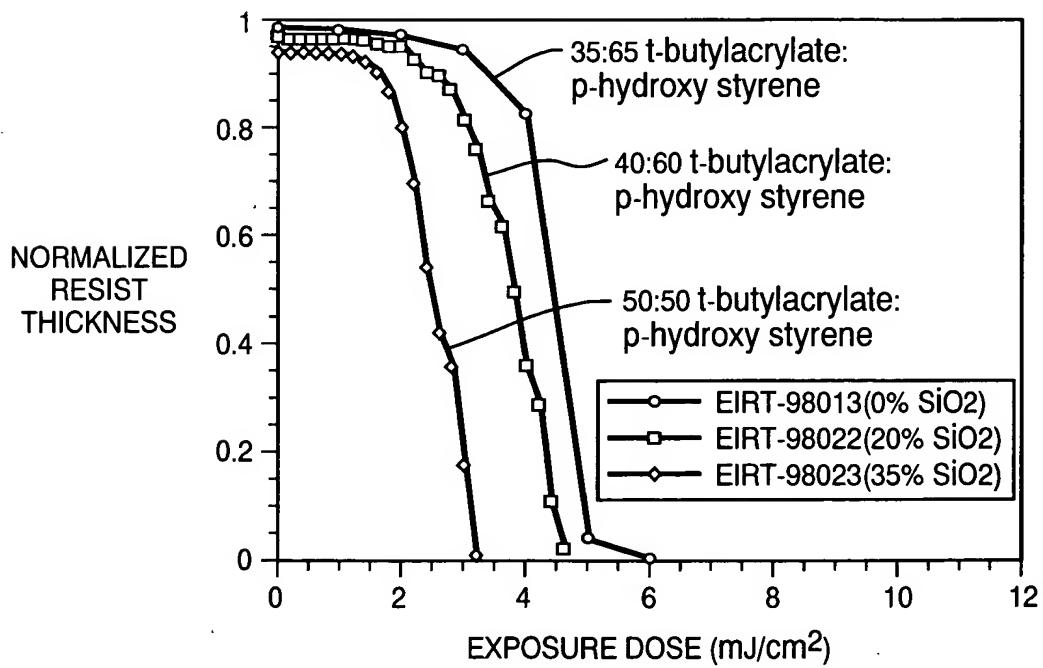
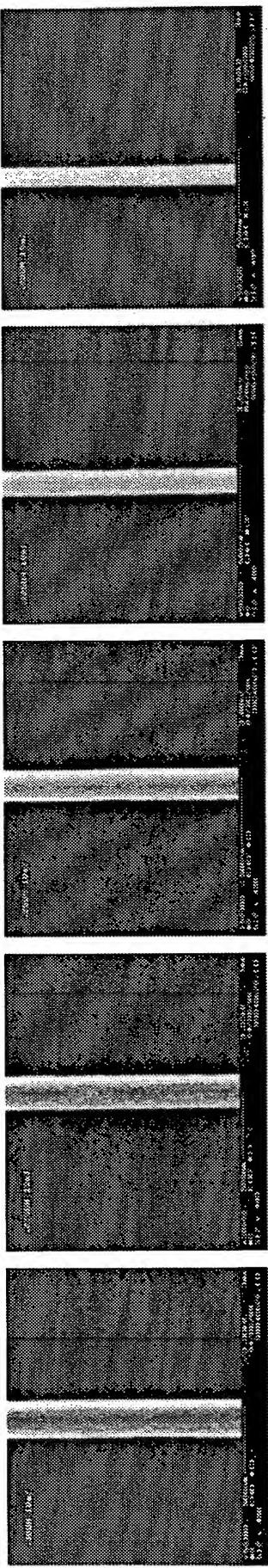
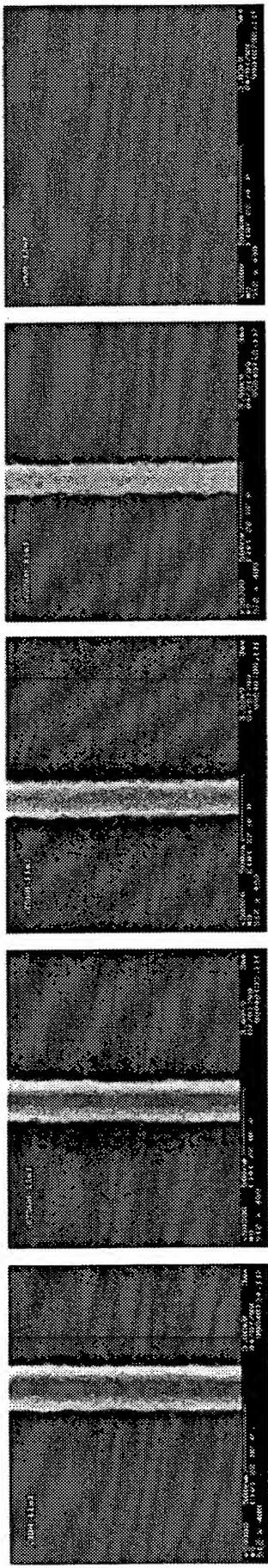


FIG. 5

EIRT 98013 RESIST (0% SiO₂) PREPARED FROM 35:65 T-BUTYLACRYLATE:P-HYDROXYSTYRENEEIRT 98022 RESIST (20% SiO₂) PREPARED FROM 40:60 T-BUTYLACRYLATE:P-HYDROXYSTYRENE

300 nm 275 nm 250 nm 225 nm

200 nm

FIG. 6